1989—Volume 136
Author and Subject Index
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The Computer-Derived 1989 Journal Index

The Publication Committee of the Society recommended the use of a computer-derived index in 1968, and this practice is planned to be continued. These indices refer only to *Journal* articles, reviews, brief communications, discussions, and news and reviews listed in the contents pages. They do not include meeting papers, abstracts, and news items. These indices were prepared for the *Journal* by Amron Information Services, Union, New Jersey.

Using the Index

1. Given any author, go directly to his name in the author and title index to find the full paper title with a page citation or, if he is a secondary author, to find a cross-reference to a primary author.
2. Given any topic, go to the subject index and search for the key word itself.
3. For a detailed explanation and meaning of symbols and abbreviations, see the sample pages before the individual author and title index and subject index.
4. Chemical formulae cannot be reproduced directly because the conventional computer printout appears in capital letters only. For example, Bi3 could be three atoms of bismuth or boron triiodide.

The Publication Committee will appreciate comments on the usefulness and accuracy of this index.

LEE P. HUNT
Chairman
Publication Committee

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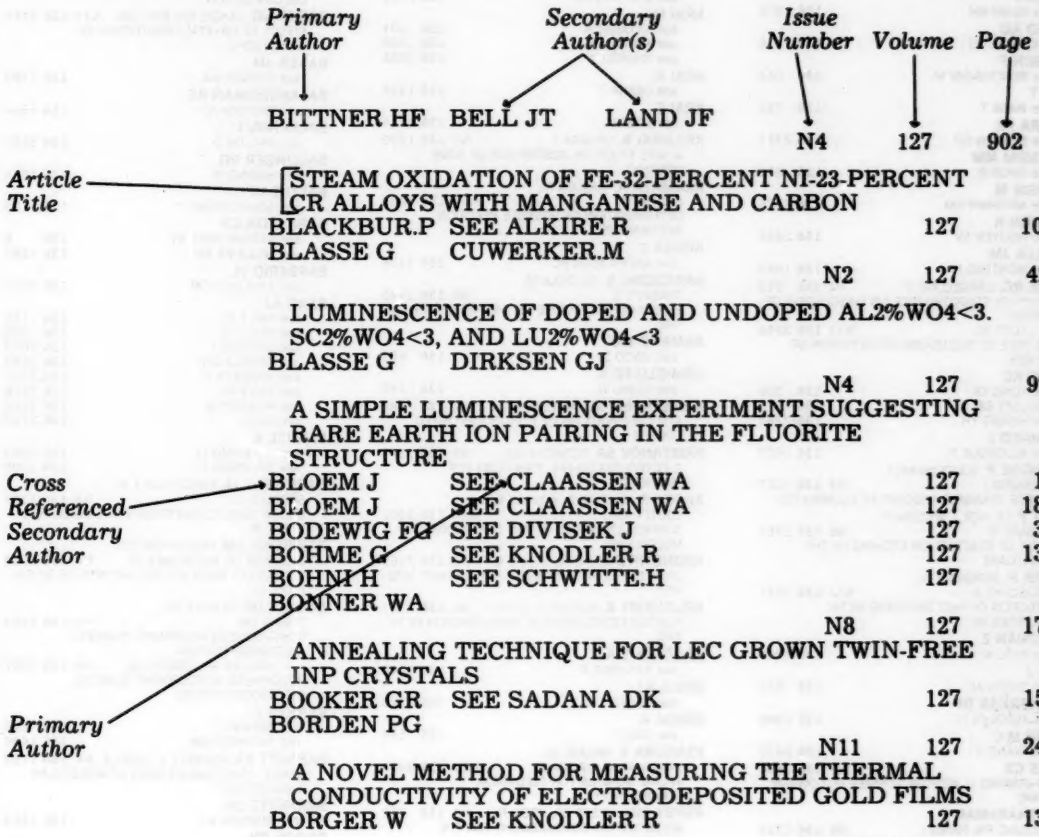

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